

METHOD FOR FORMING PATTERNED ITO STRUCTURE BY USING PHOTSENSITIVE ITO SOLUTION

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ABSTRACT OF THE INVENTION

A method for forming a patterned ITO structure by using a photosensitive ITO solution is provided. By mixing both the ITO and photosensitive material to form a photosensitive ITO solution on a substrate, a patterned ITO structure is available by directly exposing and developing the photosensitive ITO layer. Significantly, no photo-resist layer is required.

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